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- (71) Applicant (for all designated States except US): THOMAS WEST, INC. [US/US]; 470 Mercury Drive, Sunnyvale, CA 94805 (US).
- (72) Inventors: WU, Guangwei; 1063 Plymouth Drive, Sunnyvale, CA 94087 (US). KIRTLEY, Steve; 14702 Horseshoe Drive, Saratoga, CA 95070 (US). WEST, Thomas, E.; 187 Goya Road, Portolla Valley, CA 94028 (US).
- (74) Agent: WILLIAMS, Larry; 3645 Montgomery Drive, Santa Rosa, CA 95405 (US).

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(54) Title: STACKED PAD AND METHOD OF USE

(57) Abstract: The following is a description of a stacked pad (15) for chemical mechanical polishing and/or planarizing substrates. In one embodiment, the stacked pad includes a top pad (20) and a subpad (40) where the modulus of the top pad (20) substantially equals the modulus of the subpad (40). Also presented are methods of using the stacked pad (15) which include methods of chemical mechanical polishing and/or planarization, and products of using the stacked pad.

